

Abstract of the Disclosure

An optical arrangement is equipped with lenses (22, 42) of double-refracting optically single-axis material in a pupillary plane (21, 41) and in tangentially polarized light or radially linearly polarized light. In this way, and for 157 nm lithography, MgF_2 is usable as additional lens material with a deviating refracting index for achromatization with $\text{CaF}_2/\text{BaF}_2$.